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HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION PROCESS

Appl. No. : 09/991,196 Confirmation No. 3908
Applicant : Chih-Chien Liu et al.
Filed : November 20, 2001
TC/A.U. : 1796
Examiner : SERGENT, RABON A
Docket No. : NAUP1068USA3
Customer No. : 27765

Commissioner for Patents
P.O. Box 1450
Alexandria VA 22313-1450

AMENDMENT

Sir:

5 In response to the NOTICE OF ALLOWANCE AND FEE(S) DUE on December 21, 2009. According to 37 CFR 1.312, applicant would like to amend some typos, which merely embody the correction of formal matters without changing the scope of the claims. Please amend the above -identified applications as follow:

10 **Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 8 of this paper.